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Front Matter: Volume 9633

, "Front Matter: Volume 9633," Proc. SPIE 9633, Optifab 2015, 963301 (23 October 2015); doi: 10.1117/12.2222197

SPIE.

Event: SPIE Optifab, 2015, Rochester, New York, United States

PROCEEDINGS OF SPIE

Optifab 2015

Julie L. Bentley
Sebastian Stoebenau
Editors

12–15 October 2015
Rochester, New York, United States

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Published by
SPIE

Volume 9633

Proceedings of SPIE 0277-786X, V. 9633

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Optifab 2015, edited by Julie L. Bentley, Sebastian Stoebenau, Proc. of SPIE Vol. 9633, 963301
© 2015 SPIE/APOMA · CCC code: 0277-786X/15/\$18 · doi: 10.1117/12.2222197

Proc. of SPIE/APOMA Vol. 9633 963301-1

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Author(s), "Title of Paper," in *Optifab 2015*, edited by Julie L. Bentley, Sebastian Stoebe, Proceedings of SPIE Vol. 9633 (SPIE, Bellingham, WA, 2015) Six-digit Article CID Number.

ISSN: 0277-786X
ISSN: 1996-756X (electronic)
ISBN: 9781628418385

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) • Fax +1 360 647 1445
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